

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

Claim 1. (canceled).

2. (currently amended): A photosensitive composition comprising a compound that generates an acid upon irradiation of an actinic ray or radiation (Component A), a resin that is decomposed by the action of an acid to increase solubility in an alkali developing solution (Component B), a performance adjusting agent (Component C) and a solvent (Component D), wherein a, b, c and d, which represents contents of Component A, Component B, Component C and Component D in terms of part by weight respectively, satisfy formulae (1) and (3) shown below, provided that c may be 0[[]]:

$$(a + b + c)/(a + b + c + d) = 0.03 \text{ to } 0.10 \quad (1)$$

$$a/(a + b + c) = \underline{0.05 \text{ to } 0.15} \quad (3).$$

Claims 3. - 6. (canceled).

7. (currently amended): The photosensitive composition as claimed in Claim 1 2, wherein Component B is a resin containing a fluorine atom.

8. (currently amended): The photosensitive composition as claimed in Claim ~~4~~ 2, wherein Component B is a resin containing a phenolic hydroxy group.

Claim 9. (canceled).

10. (currently amended): The photosensitive composition as claimed in Claim ~~4~~ 2, wherein Component C is a basic compound.

11. (currently amended): The photosensitive composition as claimed in Claim ~~4~~ 2, wherein Component A is a sulfonium salt.

12. (currently amended): The photosensitive composition as claimed in Claim ~~4~~ 2, wherein Component D is a solvent having an ester group.

13. (currently amended): The photosensitive composition as claimed in Claim ~~4~~ 2, wherein Component D is a solvent having a hydroxy group and/or a carbonyl group.

14. (currently amended): The photosensitive composition as claimed in Claim ~~4~~ 2, wherein Component D is a mixture of a solvent having an ester group and a solvent having a hydroxy group and/or a carbonyl group.

15. (original): The photosensitive composition as claimed in Claim 2, wherein Component B is a resin containing a monocyclic or polycyclic alicyclic hydrocarbon group.

16. (original): The photosensitive composition as claimed in Claim 2, wherein Component B is a resin containing a lactone group.

17. (original): The photosensitive composition as claimed in Claim 2, wherein Component B is a resin containing an adamantane structure having one or two hydroxy groups.

18. (new): The photosensitive composition as claimed in Claim 2, wherein a, b, c and d satisfy formula (2) shown below:

$$\frac{[(\text{Number of aromatic rings included in molecule of Component A} + 1) \times a]}{(a + b + c)} = 0.10 \text{ to } 0.40 \quad (2).$$

19. (new): The photosensitive composition as claimed in Claim 18, wherein the range on the right hand side of the formula (2) equality is from 0.15 to 0.30.

20. (new): A pattern forming method comprising:
forming a photosensitive film having a thickness of from 50 to 300 nm from a photosensitive composition as claimed in Claim 2;
exposing the photosensitive film, so as to form an exposed photosensitive film; and
developing the exposed photosensitive film.